11 SEP 2003

200304932 7

162162

(12) INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

(19) World Intellectual Property Organization
International Bureau

(43) International Publication Date
10 October 2002 (10.10.2002)

PCT

(10) International Publication Number
WO 02/078904 A1

(51) International Patent Classification[7]: B24B 37/04, 21/04

(21) International Application Number: PCT/US02/09858

(22) International Filing Date: 29 March 2002 (29.03.2002)

(25) Filing Language: English

(26) Publication Language: English

(30) Priority Data:

09/823,722	30 March 2001 (30.03.2001)	US
10/029,958	21 December 2001 (21.12.2001)	US

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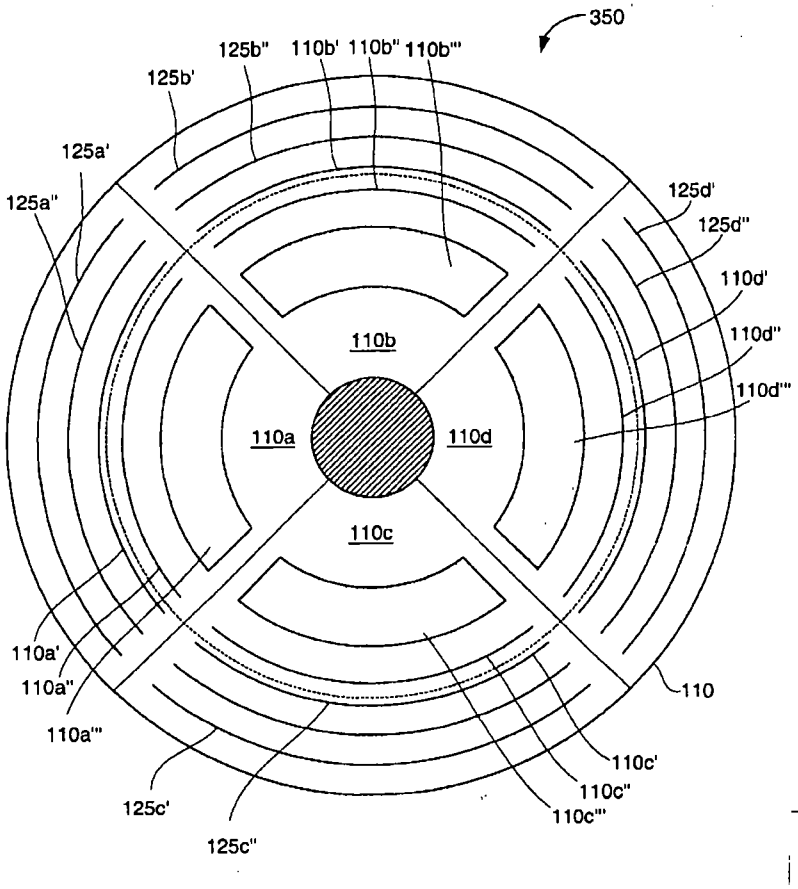
(81) Designated States *(national)*: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU,

[Continued on next page]

(54) Title: SUPPORT FOR A POLISHING BELT



(57) Abstract: An invention is provided for a platen (110) for use in a CMP system. The platen (110) is arranged below a linear polishing pad (102) and designed to apply a controlled fluid flow to the underside of the linear polishing pad. The platen (110) includes a leading zone containing a first plurality of output holes where the leading zone oriented more proximate to an upstream region of the linear polishing pad (102). The platen (110) also includes a trailing zone containing a second plurality of output holes where the trailing zone is oriented more proximate to a downstream region of the linear polishing pad (102). The leading zone and the trailing zone are independently controlled and designed to output the controlled fluid flow independently from each of the first plurality of output holes and the second plurality of output holes.

WO 02/078904 A1

ACTION

CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, OM, PH, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VN, YU, ZA, ZM, ZW.

(84) **Designated States** *(regional)*: ARIPO patent (GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW), Eurasian patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European patent (AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, TR), OAPI patent (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

Published:
— *with international search report*

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